

METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST

Application No. 09/919,868

Inventor: LU, YEN-TING

*Replacement Sheet*

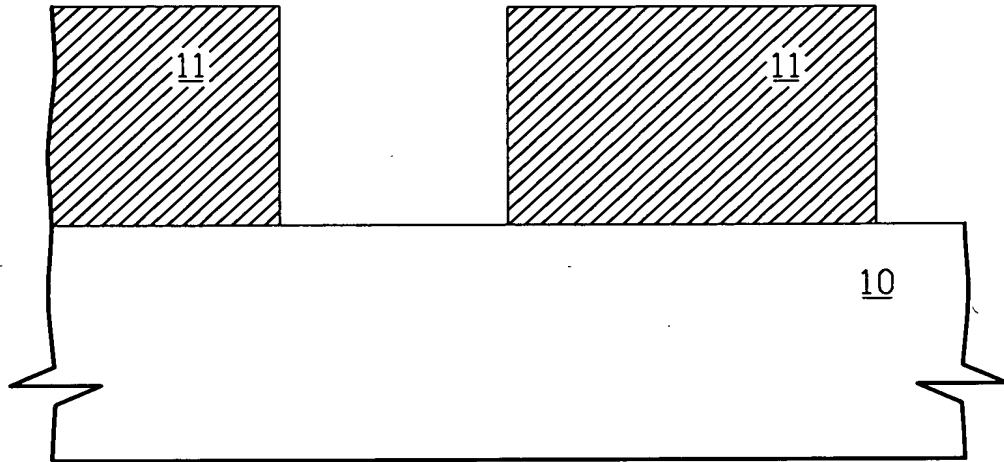


FIG.1A(Prior Art)

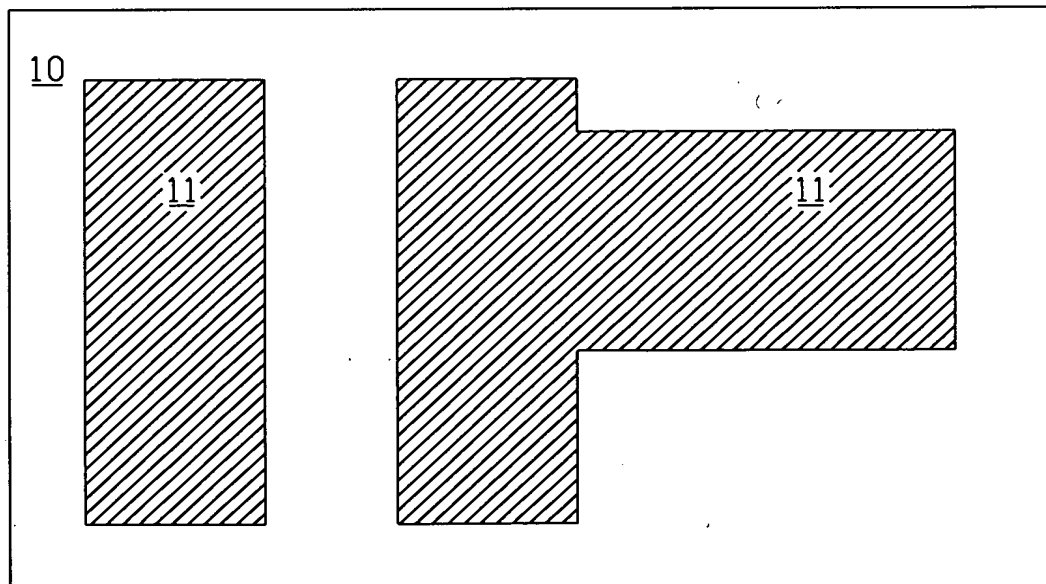


FIG.1B(Prior Art)

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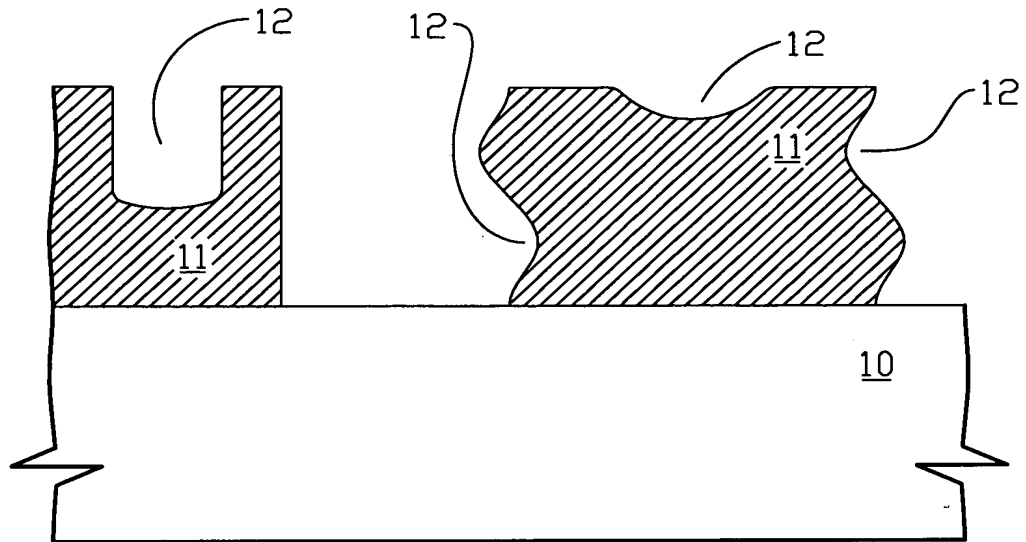


FIG.1C(Prior Art)

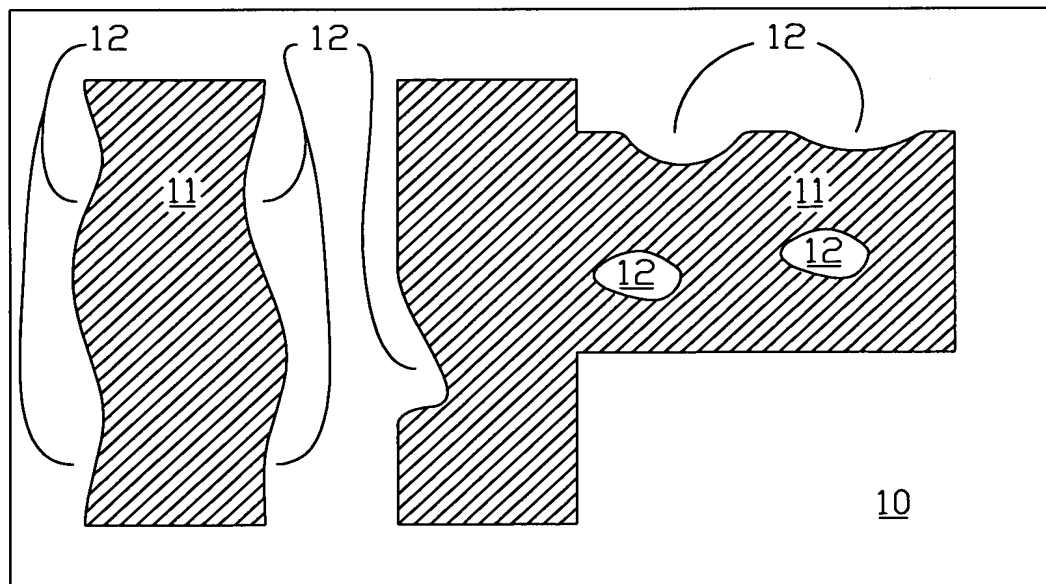


FIG.1D(Prior Art)

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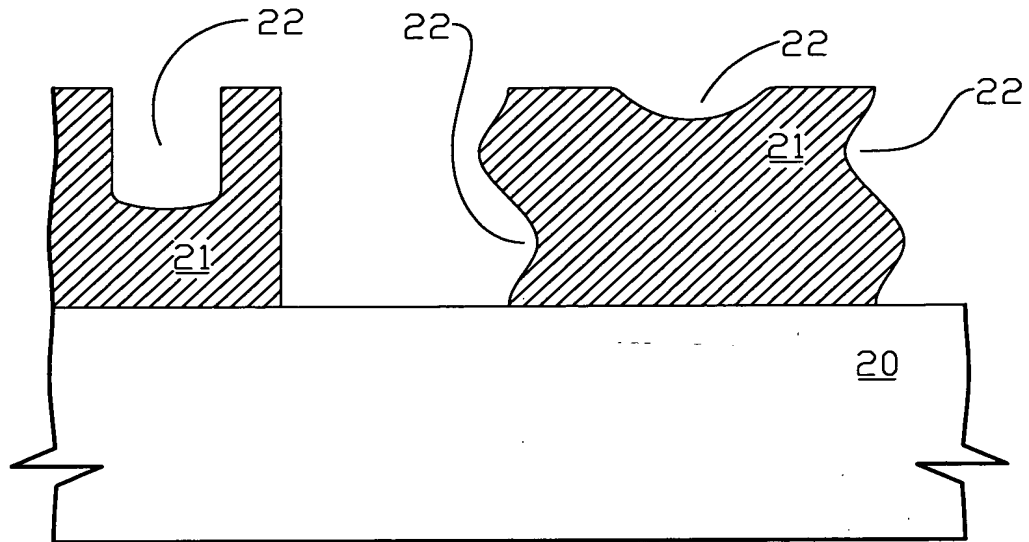


FIG. 2A

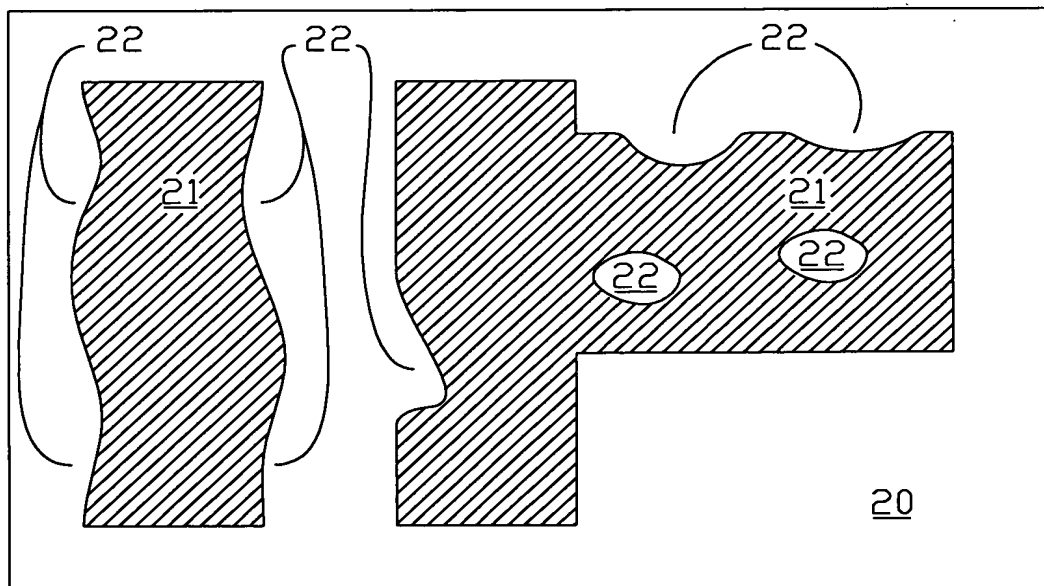


FIG. 2B

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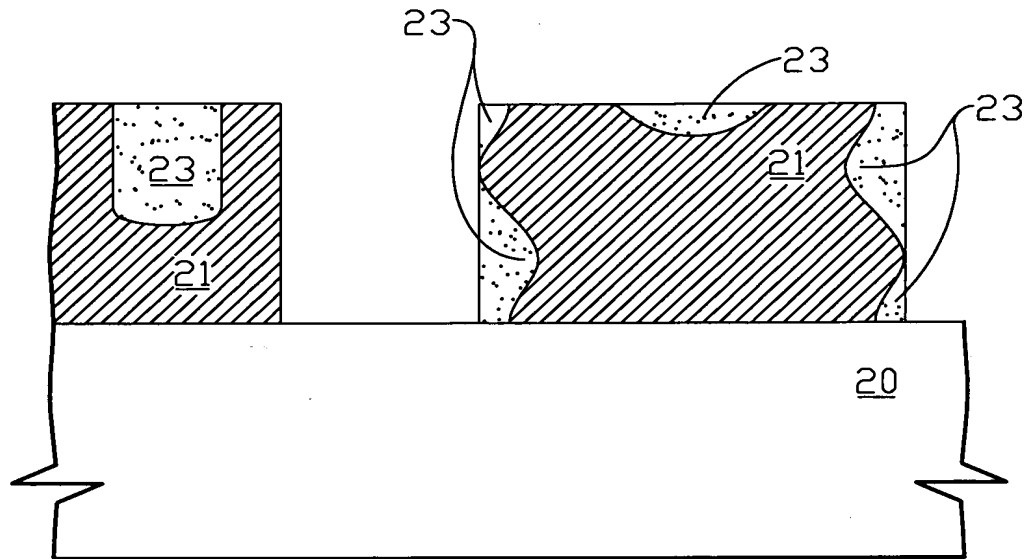


FIG.2C

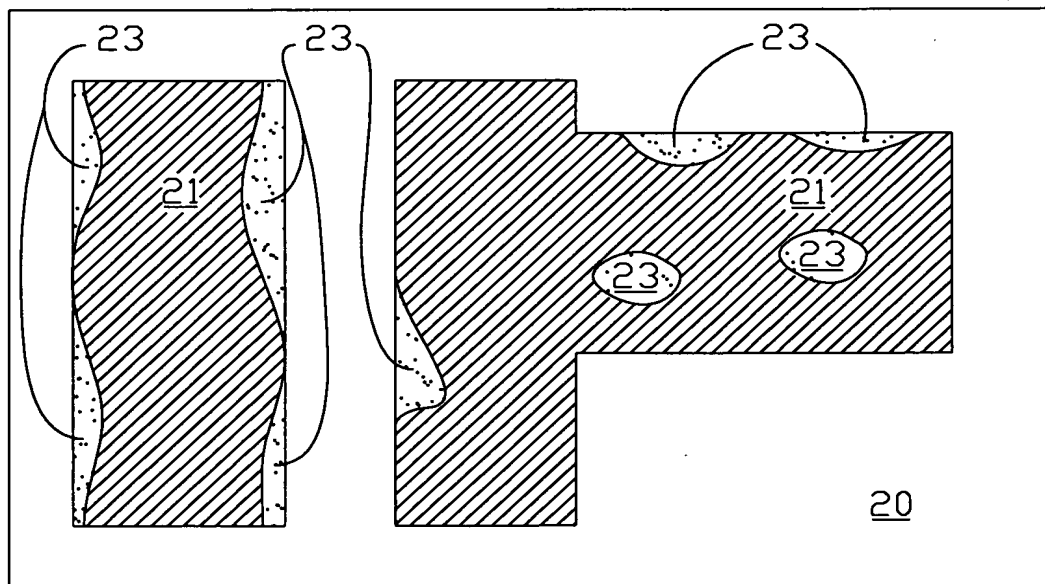


FIG.2D



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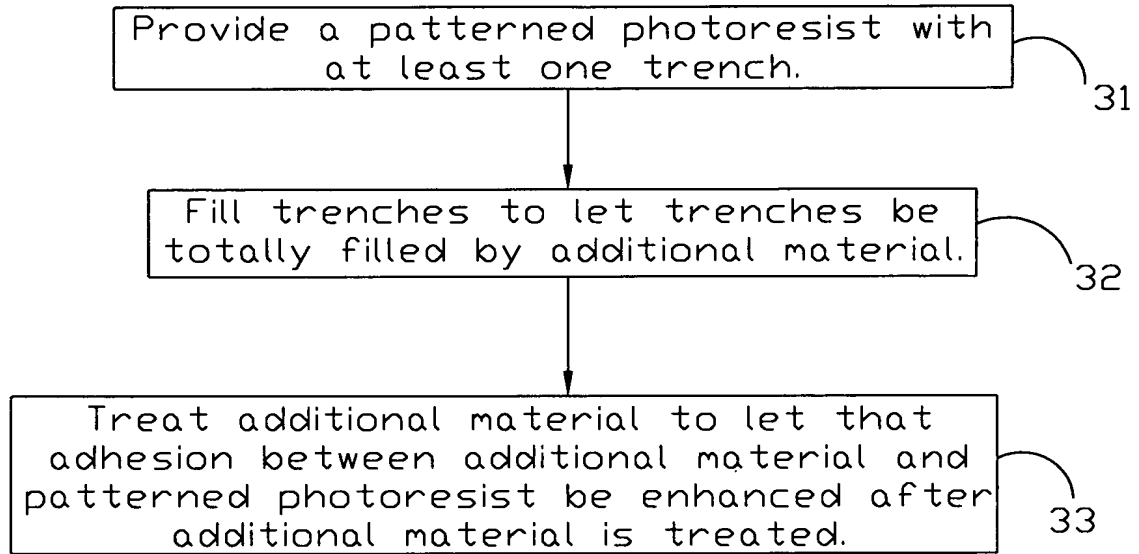


FIG.3A

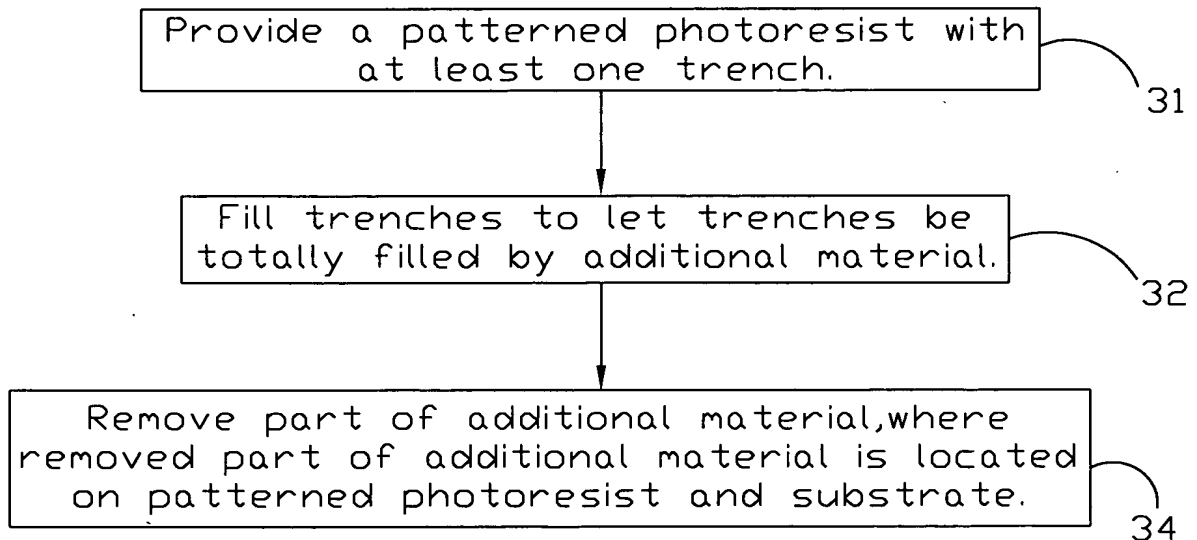


FIG.3B

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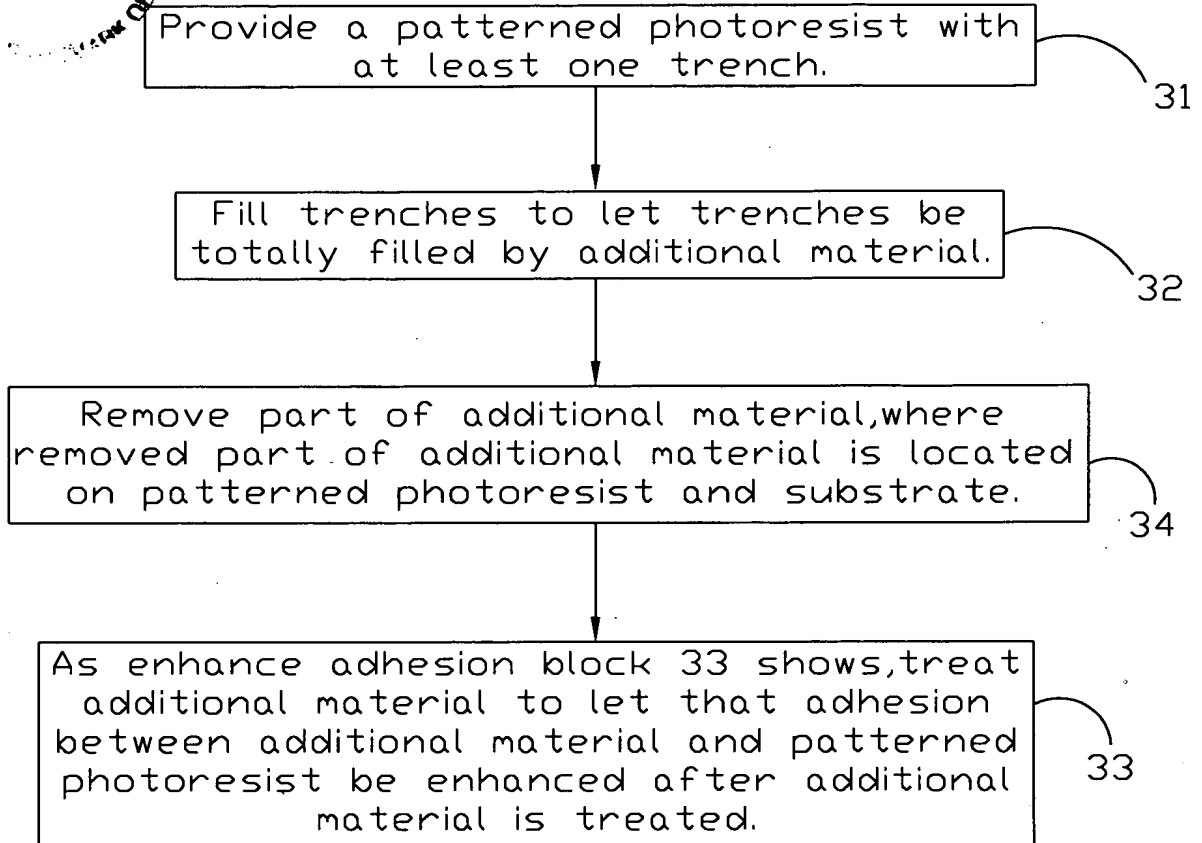
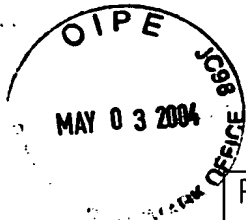


FIG.3C